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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: MANABE et al.

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Page 1 of 1

Examiner: Not Assigned

Group Art Unit: 2812

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR					
	BR					
	CR					
	DR					
	ER					
	FR					
	GR					
	HR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
Gu	IR	S63-188938	08/1988	JAPAN	MANABE	x			
	JR	02-042770	02/1990	JAPAN	MANABE	x			
	KR	58-200527	11/1983	JAPAN	ISHII	x			
Gu	LR	60-175468	09/1985	JAPAN	KAWABATA	x			
	MR								
	NR								
	OR								
	PR								
	QR								
	RR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

Gu	SR	Tietjen et al., "Vapor Phase Growth Technique and System for Several III-V Compound Semiconductors," Electronic Research Center, March 1969, 11 pp.			
	TR	Sze, "Physics of Semiconductor Devices," Wiley Interscience, 1969, pp. 42-43.			
	UR	Azoulay et al., "MOCVD n-Type Doping of GaAs and GaAlAs Using Silicon and Selenium and Fabrication of Double Heterstructure Bipolar Transistor," Journal of Crystal Growth, 68 (1984) pp. 453-460.			
	VR	Hiramatsu et al., "Effects of Buffer Layer in MOVPE Growth of GaN Film on Sapphire Substrate," Nagoya University, November 6, 1988, pp. 334-342.	x		
	WR	Khan et al., "Effect of Si on Photoluminescence of GaN," Solid State Communications, Vol. 57, No. 6, 1986, pp. 405-409.			
Gu	XR	Bass, "Silicon and Germanium Doping of Epitaxial Gallium Arsenide Grown by the Trimethylgallium-arsine Method," Journal of Crystal Growth, 47 (1979) pp. 613-618.			

Examiner: *[Signature]*

Date Considered: 12/24/02

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.